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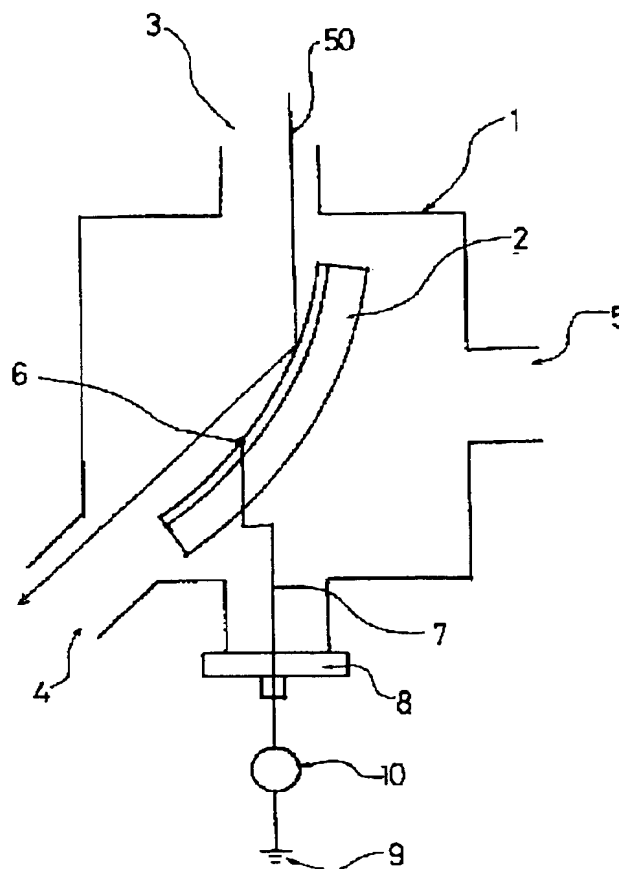
APPLICATION DATE : 06-04-92
APPLICATION NUMBER : 04084099

APPLICANT : SUMITOMO ELECTRIC IND LTD;

INVENTOR : KANIE TOMOHIKO;

INT.CL. : G01N 23/227

TITLE : MONITORING METHOD FOR MIRROR
FOR SYNCHROTRON RADIATION
BEAM



ABSTRACT : PURPOSE: To monitor a mirror for a synchrotron radiation beam by applying a synchrotron radiation beam to a mirror face and measuring a quantity of photoelectrons emitted from the mirror face.

CONSTITUTION: A mirror vessel 1 is normally connected to a reaction vessel in the case of CVD and an exposure chamber in the case of lithography through a light outgoing window 4. In the case of CVD and lithography a gas within the mirror vessel 1 is evacuated by the use of a vacuum pump and the like. Before CVD and lithography are performed in the mirror vessel 1, a synchrotron radiation beam 50 is irradiated on the mirror face of a mirror 2 in a previous condition where the mirror 2 becomes dirty and an electric current value allowed to flow on the mirror face of the mirror 2 is measured by the use of an ammeter 10. Thereafter, CVD and lithography are started and the electric current value allowed to flow on the mirror face of the mirror 2 is measured by the use of the ammeter 10 in elapse. Thereby the dirt of the mirror 2 can be monitored.

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